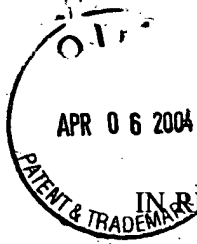


04-07-04

Express Mail No. ER452516100US  
Attorney Docket No.: AM-5264.D1



**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

IN RE APPLICATION OF: Cheng Guo et al.

SERIAL NO.: 10/792,011

FILED: March 3, 2004

FOR: STRUCTURES USEFUL IN ELECTRON BEAM  
LITHOGRAPHY

§ GROUP ART UNIT: 1756  
§ (Parent Application)

§ EXAMINER: S. R. Mohamedulla  
§ (Parent Application)

§ Attorney Docket No.:  
§ AM-5264.D1

Date: April 6, 2004

**INFORMATION DISCLOSURE STATEMENT**  
**TRANSMITTAL LETTER**

Hon. Commissioner for Patents  
P.O. Box 1450  
Alexandria, Virginia 22313-1450

Sir:


Applicants are submitting the subject Information Disclosure Statement under 37 CFR § 1.97(b)(1). This Information Disclosure Statement is being submitted within three (3) months of the filing date of the subject application.

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**CERTIFICATE OF MAILING UNDER 37 CFR § 1.10**

I hereby certify that this paper is being deposited with the U.S. Postal Service on the date shown below with sufficient postage as U.S. EXPRESS MAIL NO. ER452516100US in an envelope addressed to: Mail Stop DD, Commissioner for Patents, Alexandria, VA 22313-1450

Date: April 6, 2004


  
Shirley L. Church, Reg. No. 31,858

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Applicants do not believe that any fee is due in connection with the filing of this Information Disclosure Statement under 37 CFR § 1.97(b)(1). However, in the event that any additional fee is due, the Commissioner is hereby authorized to charge Deposit Account No. 50-1512 of Shirley L. Church, Sunnyvale, California, in the amount of such fee.

This transmittal letter is submitted in duplicate for accounting purposes.

Respectfully submitted,

  
Shirley L. Church  
Registration No. 31,858  
Attorney for Applicants

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FORM PTO-1449 U.S. Department of Commerce  
(Equivalent) Patent and Trademark Office

U.S. Application Serial No.  
10/792,011

Atty. Docket No.  
AM-5264.D1

INFORMATION DISCLOSURE  
STATEMENT BY APPLICANT

(Use several sheets if necessary)

Cheng Guo et al.  
Applicants

March 3, 2004  
Filing Date

1756  
Group

U. S. PATENT DOCUMENTS

Examiner Initial	Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate
_____	4,827,138	05/02/89	Randall *	250	492.2 R	
_____	5,899,728	05/04/99	Mangat et al. *	438	459	
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

- \_\_\_\_\_ S. D. Berger et al., "New approach to projection-electron lithography with demonstrated 0.1  $\mu$ m linewidth", Applied Physics Letters, Vol. 57, No. 2, pp. 153-155 (July 1990).
- \_\_\_\_\_ S. D. Berger et al., "Projection electron-beam lithography: A new approach", J. Vac. Sci. Technol. B, Vol. 9, No. 6, pp. 2996-2999 (Nov/Dec 1991).

Examiner \_\_\_\_\_ Date Considered \_\_\_\_\_

Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

\* Cited by the Examiner during the prosecution of the parent application, U.S. Serial No. 09/698,706.